Heidelberg µPG 101 Mask Maker



- Maximum substrate size: 6" x 6"
- Minimum substrate size: 10 x 10 mm²
- Substrate thickness: 0 to 6 mm
- Encoder resolution: 20 nm
- Optical system including highly reflective mirrors and modulator
- Real time air-gauge autofocus with dynamic range of 80 µm
- Camera system for substrate inspection and automatic alignment
- Conversion software for DXF, CIF, and GDSII files